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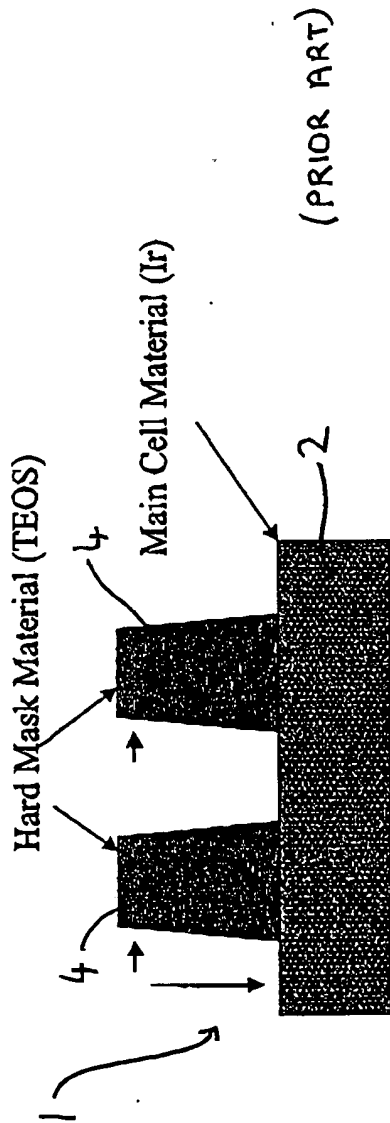


Fig. 1 After Hard Mask Open
 (Initial HM angle reducing because
 of side etching)

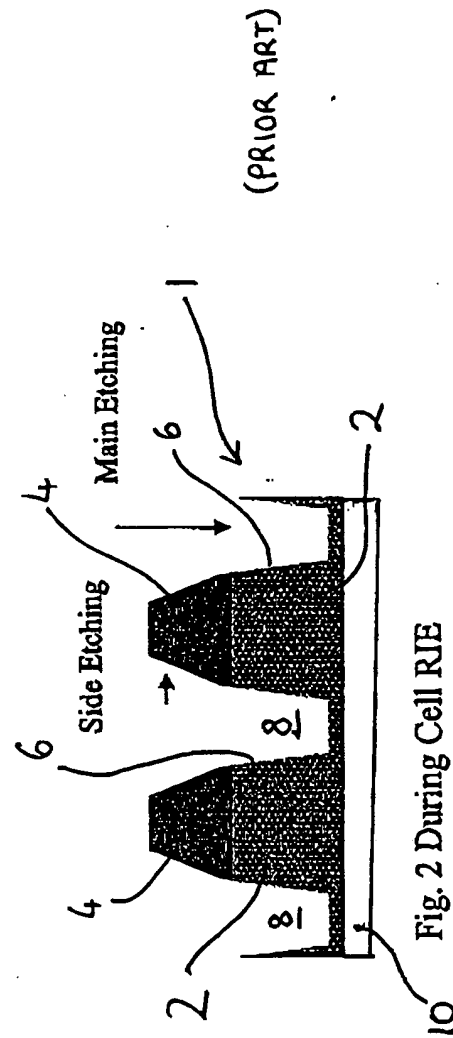
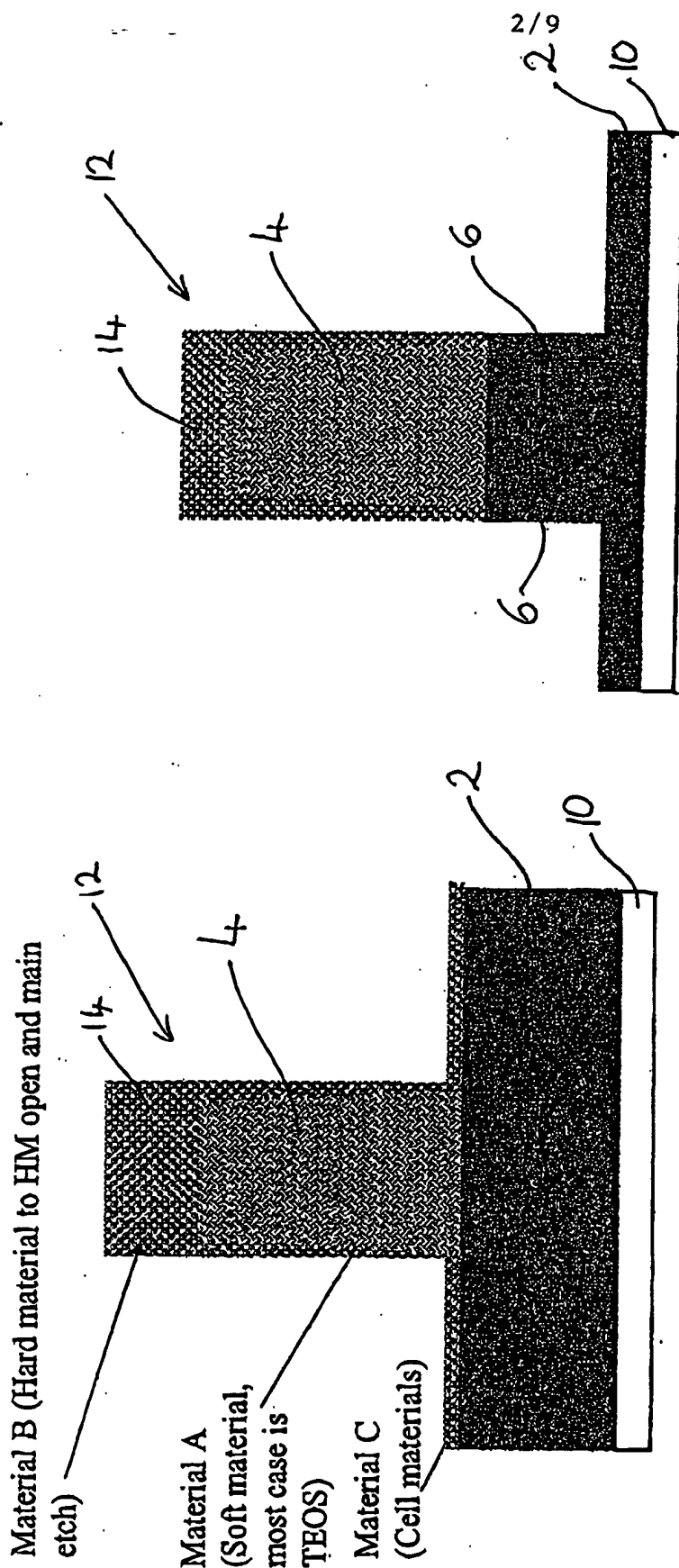


Fig. 2 During Cell RIE
 (HM angle further reduce because
 of side etching).



Before main etching (hard mask with a
 "hard shell", vertical shape)

During main etching (hard mask shape
 not change because of the shell)

Fig. 3a

Fig. 3b

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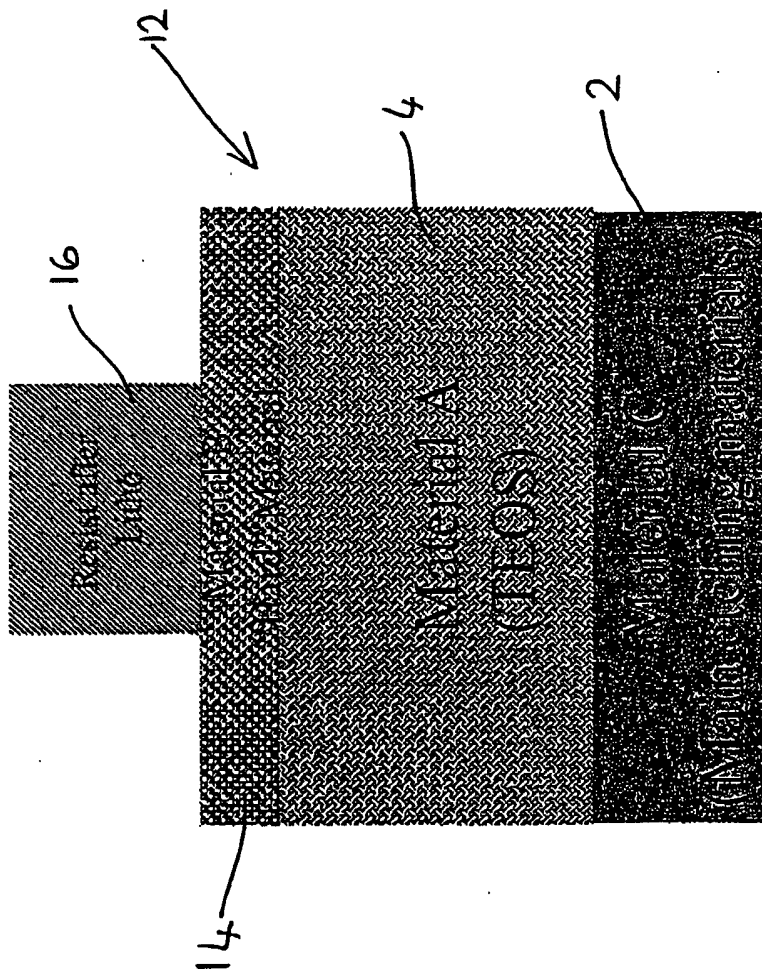


Fig. 4 Before hard mask open

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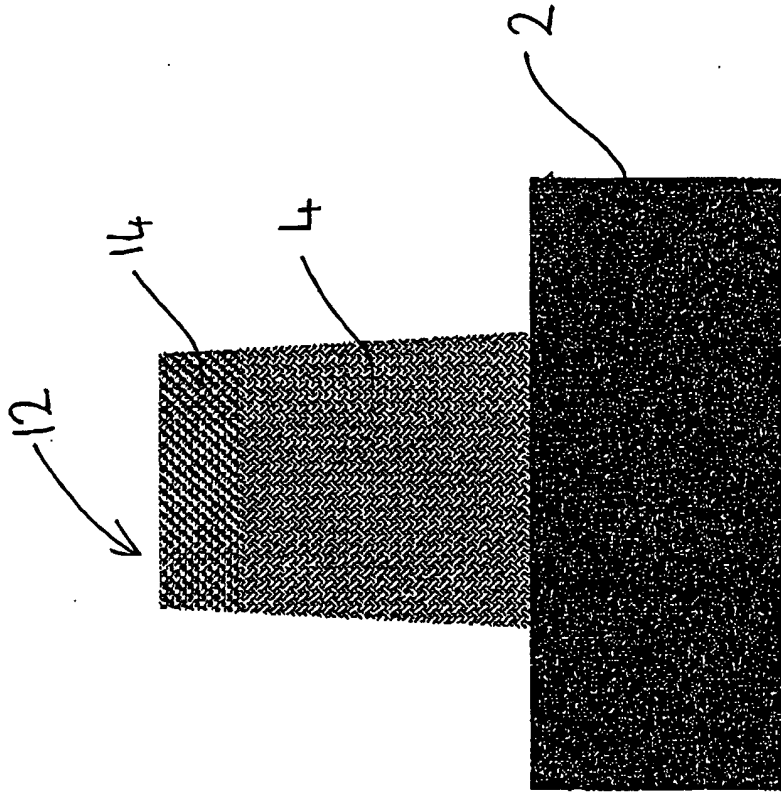


Fig. 5 After hard mask open

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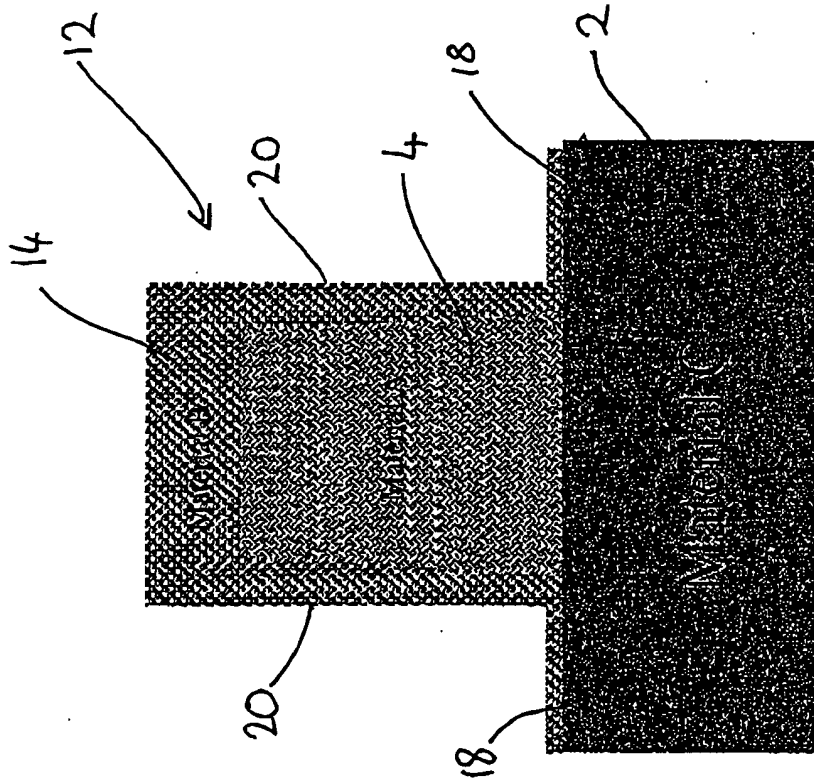


Fig. 6 Additional hard material deposit
(Before main etching)

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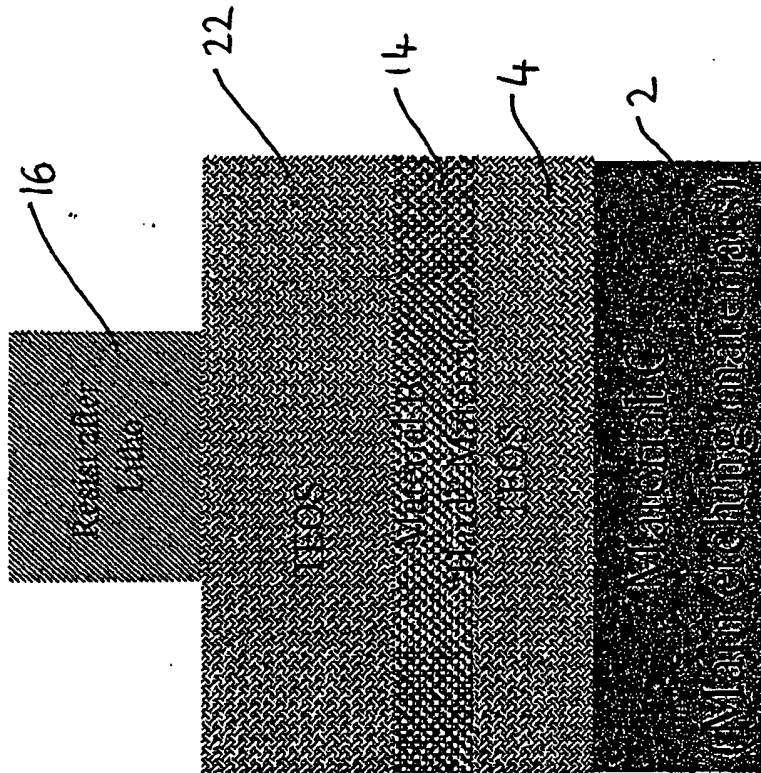


Fig. 7 Before hard mask open

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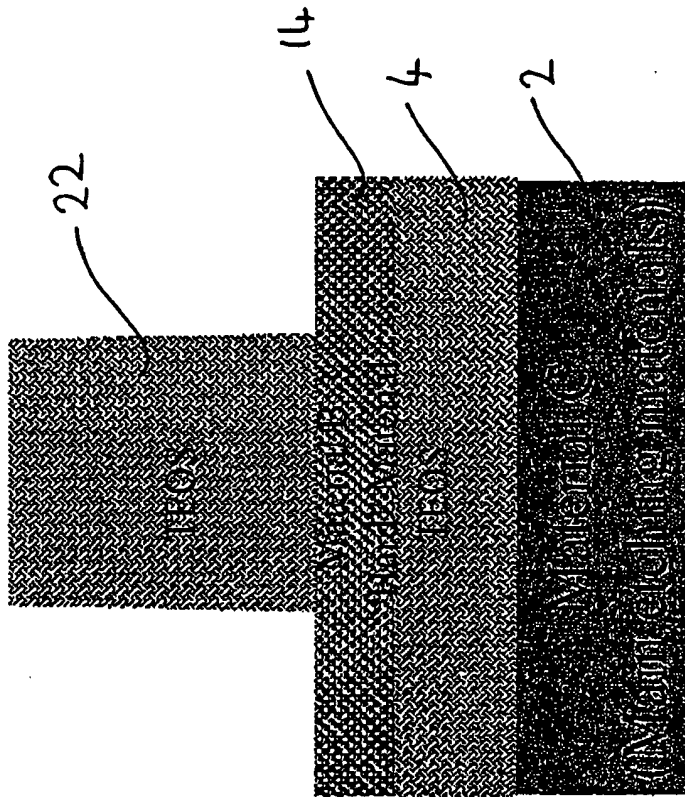


Fig. 8 Before etching material B

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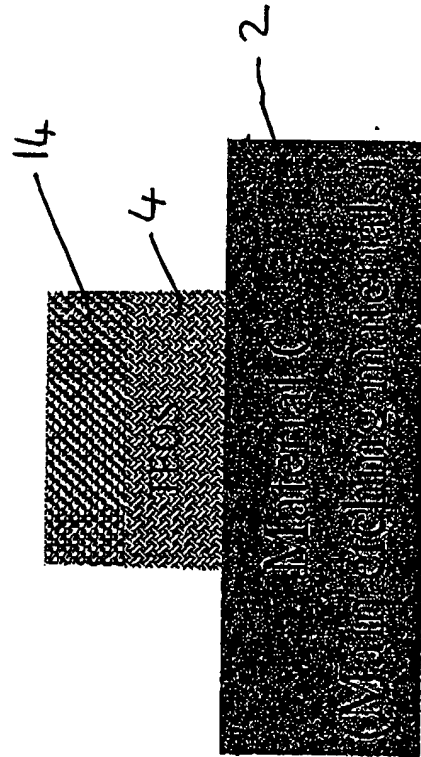


Fig. 9 Before material B deposit

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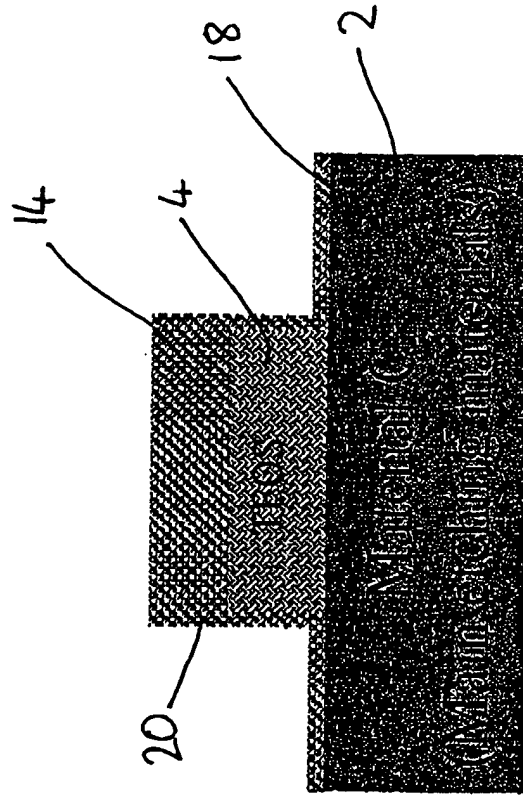


Fig. 10 After material B deposit